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TRADEMANDE
IN THE UN

N THE UNITED STATES PATENT AND TRADEMARK OFFICE BEFORE THE BOARD OF APPEALS

In Re Application of:

Inventors: Apostolos Voutsas

Serial No.: 09/893,866

June 28, 2001

Title:

Filed:

METHOD FOR FORMING

SILICON FILMS WITH TRACE)

IMPURITIES

) Group Art: 5636

) Examiner: A. Sarkar

Attorney docket No.:

SLA592

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CHNOLOGY CENTER 2800

CERTIFICATION UNDER 37 CFR § 1.8

Date 1/23/2003

Signature

Hon. Commissioner for Patents and Trademarks Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

REPLY BRIEF

This paper is a reply to an Examiner's Answer mailed by Examiner Asok Sarkar, Group Art 5636, on January 15, 2002.

ARGUMENT AND DISCUSSION

The Examiner's position, as stated in the Examiner's Answer, appears to be that the Applicant is attempting to claim a pioneering use of impurities in a silicon target used for sputtering. However, this is not what the claims actually recite. The Applicant's claims describe a relationship between the concentration of impurities in the target and a concentration of the impurities in the resultant film. None of the prior art references teach a relationship between the concentration of impurities in the target and in the resultant film. The Applicant's position is best summarized in the Appeal Brief on page 6, beginning at line 5.

Respectfully submitted,

Date: 1/23/2003

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